

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Horning et al.

Attorney Docket No. H16-16009
H000-1-1200

Serial No.: 09/873,931

Group Art Unit: 2814

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Examiner: RAO, Shrinivas

Title: APPLICATIONS OF A STRAIN-COMPENSATED HEAVILY DOPED ETCH
STOP FOR SILICON STRUCTURE FORMATION

RESPONSE TO FINAL OFFICE ACTION

TO THE COMMISSIONER OF PATENTS:

AMENDMENT AND RESPONSE